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L3: Entry 1 of 1

File: DWPI

Jan 24, 1995

DERWENT-ACC-NO: 1995-095510
DERWENT-WEEK: 199513
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TITLE: Semiconductor IC apparatus manufacturing method for MOSFET - involves shortening the channel length, while channel width of MOSFET is enlarged and metal layer is formed along with gate electrode

PATENT-ASSIGNEE:

ASSIGNEE	CODE
HITACHI LTD	HITA
NIPPON TEXAS INSTR KK	TEXI

PRIORITY-DATA: 1993JP-0190891 (July 2, 1993)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
JP <u>07022516</u> A	January 24, 1995		006	H01L021/8234

APPLICATION-DATA:

PUB-NO	APPL-DATE	APPL-NO	DESCRIPTOR
JP 07022516A	July 2, 1993	1993JP-0190891	

INT-CL (IPC): H01 L 21/82; H01 L 21/8234; H01 L 21/8242; H01 L 27/088; H01 L 27/108

ABSTRACTED-PUB-NO: JP 07022516A

BASIC-ABSTRACT:

The semiconductor IC apparatus manufacturing method involves shortening of channel length while the channel width of MOSFET is extended. Along with the gate electrode of the MOSFET, a metal wiring layer is formed through an insulating film in the upper part. The input signal is supplied from both ends of the gate electrodes.

ADVANTAGE - Realises improvement in speed without increasing area.

CHOSEN-DRAWING: Dwg.1/5

TITLE-TERMS: SEMICONDUCTOR IC APPARATUS MANUFACTURE METHOD MOSFET SHORTENING CHANNEL LENGTH CHANNEL WIDTH MOSFET ENLARGE METAL LAYER FORMING GATE ELECTRODE

DERWENT-CLASS: U11 U13

EPI-CODES: U11-D03C; U13-C02A; U13-D02;

SECONDARY-ACC-NO:

Non-CPI Secondary Accession Numbers: N1995-075299

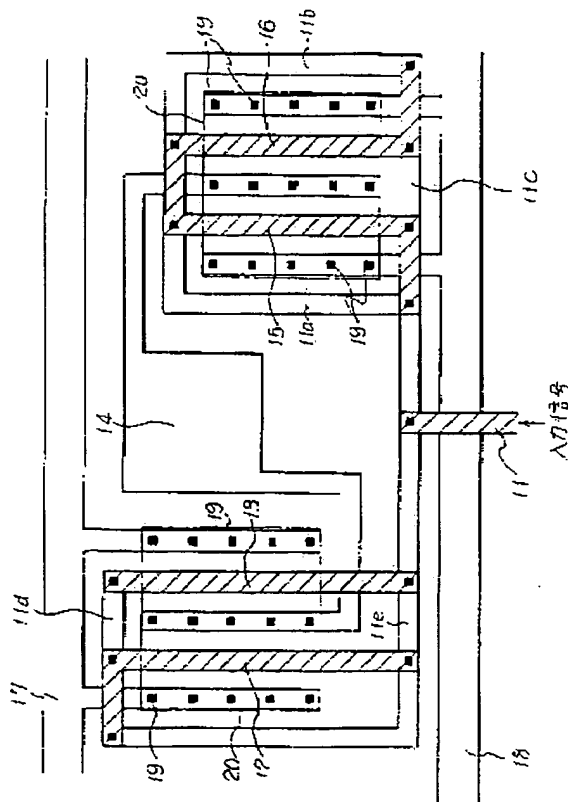
Searching by Document Number

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** Result [Utility-model] ** Format(P803) 06.Nov.2003      1/      1
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Application no/date: 1984-128916[1984/08/24]
Date of request for examination: []
Public disclosure no/date: 1986- 44854[1986/03/25]
Examined publication no/date (old law): []
Registration no/date: []
Examined publication date (present law): []
PCT application no
PCT publication no/date []
Applicant: NEC CORP
Inventor: YASUDA SADAHIRO
IPC: H01L 27/08 ,102 H01L 29/78
FI: H01L 27/08 ,321L H01L 29/78
F-term: 5F048AA00, AB04, AB05, AB07, AC03, BB05, BF03, BF15, 5F040DA02, DB03, EC07,
EC17, EC26, EJ01
Expanded classification: 422
Fixed keyword: R097
Citation:
Title of invention: CMOS output buffer
Abstract:

SUMMARY: Because an input signal is transmitted to gate electrode of CMOS output buffer by metal lines of low resistance by making CMOS output buffer have configuration, of an input waveform, a guard, incrementation of power consumption or drift of source voltage by breakthrough current or reference voltage can be prevented by incrementation of depending breakthrough current to get dull.

(Machine Translation)



Priority country/date/number: () [] ()

Classification of examiners decision/date: () []
Final examinational transaction/date: (withdrawal by no request for examination) [1988/10/25]
Examination intermediate record:
(A63 1984/ 8/24,PATENT APPLICATION UTILITY MODEL REGISTRATION APPLICATION,07100:)
(A300 1988/10/13,MAKING OF FILE WRAPPER EXTRACTION LIST OF UNREQUEST FOR EXAMINATION, :)

*** Trial no/date [] Kind of trial [] ***
Demandant: -
Defendant: -
Opponent: -
Classification of trial decision of opposition/date: () []
Final disposition of trial or appeal/date: () []
Trial and opposition intermediate record:

Registration intermediate record:

Amount of annuities payment: year
Lapse date of right: []
Proprietor: -
